

measuring system is fastened to a second frame of the positioning device which is dynamically isolated from the first frame, and in that the sub-system is fastened to the second frame.

6. (Amended) A lithographic device comprising a radiation source, a mask table, a projection system having a main axis, a substrate table, a drive unit for displacing the substrate table relative to the projection system in at least one direction perpendicular to the main axis, and a measuring system for measuring a position of the substrate table relative to the projection system, the drive unit comprising a stationary part which is fastened to a first frame of the lithographic device, while the measuring system comprises a stationary part and a movable part which is fastened to the substrate table for cooperation with the stationary part of the measuring system, characterized in that the stationary part of the measuring system is fastened to a second frame of the lithographic device which is dynamically isolated from the first frame, and in that the lithographic device comprises a further drive unit for displacing the mask table relative to the projection system in a scanning direction perpendicular to the main axis, the further drive unit comprising a stationary part which is fastened to the first frame, while the substrate table is displaceable relative to the projection system parallel to at least the scanning direction, the measuring system comprising a further stationary part which is fastened to the second frame and a further movable part which is fastened to the mask table for cooperation with the further stationary part of the measuring system for measuring a position of the mask table relative to the projection system or for measuring a position of the mask table relative to the substrate table.

8. (Amended) A lithographic device comprising a radiation source, a mask table, a projection system having a main axis, a substrate table, a drive unit for displacing the substrate table relative to the projection system in at least one direction perpendicular to the main axis, and a measuring system for measuring a position of the substrate table relative to